# ENGLISH TRANSLATION OF INTERNATIONAL APPLICATION AS FILED

### DESCRIPTION

# MANUFACTURING METHOD OF ELECTRONIC COMPONENT

## Technical Field

The present invention relates to a manufacturing method of an electronic component using a lamination chip size package (CSP), which is a type of CSP, in which a resin film is buried by heat pressing on an electronic functional element such as a SAW element bonded to a substrate.

Background Art

In the related art, in order to attain a compact and low profile package of a surface acoustic wave (SAW) filter, chip size packages (CSPs) with various kinds of structures have been developed. It is required for the CSP of the SAW to be sealed with a resin with a space formed around the vibration part of the filter.

As for a method of manufacturing such a resin-sealed package, a heat pressing process is known. Patent Document 1 and Patent Document 2, disclose a sealing technology that uses the heat pressing process. In these publications, a SAW element is mounted on a packaging substrate by flip-chip bonding so that a vibration space is formed between the packaging substrate and the SAW element attached to the packaging substrate, and the mounted SAW element is then subjected to resin sealing by the heat pressing process.

Patent Document 1: Japanese Unexamined Patent Application Publication No. 2003-17979

Patent Document 2: Japanese Unexamined Patent
Application Publication No. 2003-32061
Disclosure of Invention

However, during the sealing by the heat pressing process, voids due to air bubble entrainment tend to occur, thus causing the sealed state to be unstable. For example, there has been a tendency that, due to degradation of thermal stability during reflowing of solder, or moisture absorption with time, degradation of characteristics with time of the sealed SAW element, occurred. Moreover, when sealing was implemented in vacuum, it was possible to prevent voids from occurring, however, a large-scale apparatus for placing the entire system in vacuum has been required.

The object of the present invention is to provide a method of manufacturing an electronic component which can be manufactured by means of a simple apparatus, and in which voids and degradation of characteristics with time negligibly occur.

In order to address the above mentioned problems, the method of manufacturing an electronic component of the present invention is characterized as including: a mounting step for mounting a plurality of electronic functional

elements, each having a substrate and an electronic functional part provided on the substrate, on a collective mounting substrate; an arranging step for arranging a resin film on the electronic functional elements mounted on the collective mounting substrate; a reduced-pressure packing step for putting the electronic functional elements and the resin film mounted on the collective packing substrate in a bag with gas-barrier property, and depressurizing the inside of the bag to seal the contents inside; a sealing step for sealing the electronic functional elements with a sealing resin part originating from the resin film by causing the resin film to infiltrate between the electronic functional elements mounted on the reduced-pressure-packed collective mounting substrate; and a dividing step for dividing the collective mounting substrate having the resin-sealed electronic functional elements into individual electronic functional elements.

According to the above-described method, since electronic functional elements are sealed within a bag under reduced pressure, by means of the sealing resin part originating from the resin film, it is possible to reduce the occurrence of voids due to inclusion of air in the sealing resin, and to suppress durability degradation such as strength degradation with time or degradation of characteristics due to moisture absorption.

Moreover, in the above-described method, since only the inside of the bag should be depressurized, the bag can be depressurized by use of a simple depressurizing apparatus. Accordingly, it is possible to eliminate the use of a known large-scale apparatus for depressurizing the entire system, thus, enabling cost reduction to be achieved.

In the above-described manufacturing method, the sealing step may include a curing step for causing the resin film to infiltrate between electronic functional elements and then heating the electronic functional elements and the collective mounting substrate individually covered with a sealing resin part precursor formed from the resin film so that the sealing resin part precursor is cured into the sealing resin part, and the curing step may have a step for performing heating in a pressure-controlled hermetically sealed space.

According to the above-described method, the infiltration amount of the sealing resin can be controlled by implementing the curing step for curing by means of performing heating in the pressure-controlled hermetically sealed space, thus, enabling the infiltration amount to be adjustable.

In the above-described manufacturing method, the electronic functional element may be a surface acoustic wave element having a vibration part as the electronic functional

part on a piezoelectric substrate. In the manufacturing method, it is preferable, in the mounting step, for the vibration part to have a space between itself and the collective packaging surface, and to be arranged so as to face the collective packaging surface.

The above-described method can ensure the existence of the space required between a part to which the vibration part faces and the vibration part by adjusting the infiltration amount of the sealing resin, thus the above-described method being suitable for manufacturing a surface acoustic device.

In the above-described manufacturing method, it is preferable that the resin film contains filler, in which the maximum particle size of the particle distribution of the filler is larger than the gap between the electronic functional elements and the collective mounting substrate, and the occupancy of the filler having particle sizes larger than the gap between the electronic functional elements and the packaging collective substrate is 5 wt % or more with respect to the total amount of the filler.

According to the above-described method, the infiltration amount of the sealing resin can be adjusted by setting the characteristics of the filler as mentioned above, for example, the existence of the space required between the part to which the vibration part faces and the vibration

part, can be ensured, thus enabling suitability of the method for manufacturing the surface acoustic device.

In the above-described manufacturing method, the sealing step may further have a thermo-compression bonding step for heating the resin film to cure the resin film and for applying pressure to the resin film by means of a roller or a press machine. According to the above method, applying pressure to the resin film by means of the roller enables sealing by the resin film to be more rapid.

In the above-described manufacturing method, the arranging step may have a step for adhering a parting sheet on one surface of the resin film, and a step for arranging the resin film on the collective mounting substrate having an electronic functional element mounted thereon, so that the parting sheet side of the resin film faces the outside.

According to the above method, the parting sheet is arranged by heating during softening of the resin film or curing of the sealing resin formed from the resin film in such a way that adherence of the sealing resin and the bag can be avoided, thus enabling the manufacturing to be easier.

In the above-described manufacturing method, it is desirable for the surface roughness of the resin film side of the parting sheet to be in the range of 0.01  $\mu\text{m}$  to 10  $\mu\text{m}$ . According to the above method, by causing the surface roughness of the resin film side of the parting sheet to be

in the range of 0.01  $\mu m$  to 10  $\mu m$ , the surface roughness of the top of the sealing resin can also be in the range of 0.01  $\mu m$  to 10  $\mu m$ , thus enabling improvement of the recognition rate of printing with respect to the top.

In the above-described manufacturing method, the mounting step may be a flip-chip bonding step for mounting a plurality of the electronic functional elements through bumps by flip-chip bonding.

In the above-described manufacturing method, the bag should have a multi-layered structure having a thermoplastic resin layer as an innermost layer and a heat-resistant resin layer with a higher heat resistance and a gas-barrier property than those of the thermoplastic resin layer as an outermost layer. According to the above method, it is possible to provide the heat sealing property to the bag more surely by employing a multi-layered structure for the bag.

As described above, the method of manufacturing an electronic component according to the present invention is a method including: a reduced-pressure packing step for putting electronic functional elements mounted on a collective mounting substrate and a resin film in a bag with a gas-barrier property to seal the contents inside; and a sealing step for sealing the electronic functional elements with a sealing resin part formed from the resin film by

causing the resin film to infiltrate between the electronic functional elements mounted on the reduced-pressure-packed collective mounting substrate by utilizing the pressure difference between the inside and the outside of the bag.

Therefore, since, in the above method, the occurrence of voids can be reduced due to the fact that the infiltration occurs under reduced pressure, and the durability degradation such as strength degradation with time or degradation of characteristics due to moisture adsorption can be suppressed, and since only the inside of the bag should be under reduced pressure, the above method can achieve the reduced-pressure state by means of a simple depressurizing apparatus, eliminating the known large-scale apparatus for depressurizing the entire system, thus, resulting in cost reduction.

Brief Description of the Drawings

- FIGs. 1 (a) to (e) are views showing steps of a method of manufacturing an electronic component according to one embodiment of the present invention.
- FIG. 2 is a sectional view of a SAW device as an electronic component used in the embodiment of the present invention.
- FIG. 3 is a schematic constitution view showing a vacuum packing step in the embodiment of the present invention.

- FIG. 4 is a schematic constitution view showing a curing step in the embodiment of the present invention.
- FIG. 5 is a sectional view showing a step of the manufacturing method according to another embodiment of the present invention.
- FIG. 6 is a graph showing the relationship between the surface roughness of the top of the sealed resin of a SAW device as an electronic component used in one embodiment of the present invention and the recognition rate for the laser printing on the top.
- FIG. 7 is a sectional view showing another example of the electronic component used in the present invention.
- FIG. 8 is a schematic constitution view showing another example of the infiltrating step according to the present invention.
- FIG. 9 is a schematic constitution view showing still another example of the infiltrating step according to the present invention.
- FIG. 10 is a view showing the change of the infiltration amount in the space between the vibration part of the sealing resin and the packaging substrate when the occupancy of filler particles of a size larger than the gap between the SAW element and the collective mounting substrate with respect to the total amount of filler is changed.

### Reference Numerals

- 1 packaging substrate
- 2 SAW element (electronic component)
- 3 bump electrode
- 4 sealing resin part
- 4a sealing resin precursor
- 9 virtual scission line
- 11 collective mounting substrate
- 12 resin film
- 13 bag

Best Mode for Carrying Out the Invention

Hereinafter, based on FIGs. 1 to 9, the embodiments of the present invention will be described on the basis of FIGs. 1 to 9.

First, in a SAW element CSP manufactured according to a method of manufacturing an electronic component of the present invention, a SAW element (electronic functional element) 2 is mounted on a packaging substrate 1 by flipchip bonding. In this case, in order not to disturb the vibration of the SAW element, the SAW element is mounted so as to ensure the existence of a space 5.

The above packaging substrate 1 is composed of a material with an electric insulation property, for example, alumina, glass-epoxy etc., ceramics, resin, or the like.

The packaging substrate 1 is provided with lands 1a, or

electrodes, for connection to the SAW element 2, on the surface facing the SAW element 2; via-holes 1b penetrating through the packaging substrate 1 in the thickness direction; and external terminals 1c each electrically connected to the corresponding land 1a through the corresponding via-hole 1b.

The SAW element 2 has at least one comb electrode part as an electronic functional part, or a vibration part 2b, disposed on a piezoelectric substrate 2a. The vibration part 2b in the SAW element 2 is a region through which surface acoustic waves propagate. As for bonding of bump electrodes 3 formed on the packaging substrate 1 and the SAW element 2, or the land 1a, Au-Au bonding, solder bonding, plating bump bonding, or the like are listed as being suitable.

Moreover, the vibration part 2b having a comb electrode part is formed on a surface of the SAW element 2 facing the packaging substrate 1. The vibration part 2b faces the space 5 formed according to the height of the bump electrode 3. Accordingly, due to the presence of the space 5, the excitation and propagation of the surface acoustic waves in the vibration part 2b are not disturbed.

At this time, the gap between the SAW element 2 and the packaging substrate 1 is set to be of the order of 19  $\mu m\,.$  As for the gap, it should be set as required, and should not

be interpreted as being specifically limited, however, it is preferable to be 5  $\mu m$  or more. If it is less than 5  $\mu m$ , the surface of the SAW element 2 and the packaging substrate 1 may come into contact with each other due to warping or unevenness etc. of the packaging substrate 1.

Moreover, as mentioned above, the bump electrodes 3 electrically connect the SAW element 2 and the packaging substrate 1, however, in addition to the bump electrodes 3, a bump electrode for simply mechanically fixing the SAW element 2 to the packaging substrate 1 may be provided. Further, a bump electrode for maintaining the gap between the packaging substrate 1 and the SAW element 2 may be provided.

In the SAW element CSP, the SAW element 2 is covered with the sealing resin part 4. As for a material of the sealing resin part 4, it is not specifically limited as long as it has a sealing property and an adhesion property, however, for example, thermosetting or thermoplastic resin such as an epoxy-based, polyimide-based, polyolefin-based, silicon-based, or phenol-based one can be used. In this embodiment, epoxy-based resin is used. The curing temperature of the above epoxy-based resin is 150°C, however, when the resin is epoxy-based one, its curing temperature is approximately 80°C to 200°C.

Further, the material constituting the sealing resin

part 4 may contain filler. As for the filler, it is not specifically limited, however, suitable inorganic fillers commonly used for resin composition can be used. As for such inorganic fillers, metallic oxide powder such as silica, alumina, magnesia, or calcium oxide, are listed as being suitable. The shape of the filler particles may be either spherical or amorphous.

It is preferable for the filler that the maximum filler particle size is larger than the gap between the SAW element 2 and the collective mounting substrate 11, and is to 1/2 or less, more preferably 1/4 or less of the smaller gap between neighboring SAW elements 2, and the occupancy of the filler having a particle size larger than the gap between the SAW element 2 and the collective mounting substrate 11 with respect to the total amount of filler is 5 wt % or more.

When the particle size of the filler is within the above specified preferable range, the space 5, between the vibration part 2b and the packaging substrate 1, especially in a region facing the vibration part 2b, is protected from the infiltration of the sealing resin part 4, namely control of the filler ensures the existence of a gap. Accordingly, the propagation of the surface acoustic waves is ensured in the vibration part 2b on the piezoelectric substrate 2a. Referring to FIG. 10 and Table 1, this will be described on the basis of specific experimental results. FIG. 10 and

Table 1 show the change of the infiltration amount of the sealing resin part 4 into the space 5 between the vibration part 5 and the packaging substrate 1, especially into the region facing the vibration region, when the occupancy of filler with a particle size larger than the gap is changed in manufacturing of the surface acoustic wave device of this embodiment. In addition, in FIG. 10, the infiltration amount is represented by relative infiltration amount (%). The infiltration amount rate of the sealing resin part 4 in the space 5 is defined as 100 % if the occupancy of filler with a particle size larger than the gap is zero wt %, the relative infiltration amount (%) of the infiltration amount is intended to denote the resin infiltration amount rate of 100% in the space 5.

Table 1

occupancy of filler having a	relative infiltration
particle size larger than	amount (%)
gap (wt %)	
0	100
3	47
5	20
10	22
20	19

As is clear from FIG. 10 and Table 1, if the occupancy

of the filler with a particle size larger than the gap is set to 5 wt % or more with respect to the total amount of filler, it is known that the infiltration amount of the sealing resin part 4 into the space 5 can be suppressed.

The particle size is defined by the size of the sieve openings when the filler is passed through a sieve with sieve openings. The particle size may be defined by a classifier (the difference in scattering due to air, or sedimentation velocity) other than the sieve.

Next, the method of manufacturing the surface acoustic wave device (electronic component) according to this embodiment will be described with reference to FIGs. 1(a) to (e), and FIGs. 2 to 4. First, the manufacturing method is a method that includes at least a mounting step, an arranging step, a vacuum (reduced-pressure) packing step, a sealing step, and a dividing step, and the steps being implemented in this order.

First, in the manufacturing method, a step for forming the vibration part 2b, an electrode pad (not shown), or a wiring pattern to electrically connect both of the parts on the piezoelectric substrate 2a by a lithography process using conductive metal, for example, aluminum, to obtain the SAW element 2, is provided as a pre-step.

After the pre-step, the mounting step is implemented. As shown in FIG. 1(a), the mounting step is a step for

bonding a plurality of SAW elements 2 on the collective mounting substrate 11 with an external terminal 1c (see; FIG. 2) by flip-chip bonding. In the mounting step, depending on the chip size of the SAW element 2, several hundreds to several thousands of SAW elements 2 are mounted in a grid on the collective mounting substrate 11 of a size, for example,  $10~\rm cm \times 10~\rm cm$ . In this embodiment, the gap between the mounted neighboring SAW elements 2 is set to about 300  $\mu m$  in a smaller area, and about 800  $\mu m$  in a larger area. The gap can be changed as necessary.

Next, in the arranging step, a resin film 12 is arranged on the SAW elements 2 mounted on the collective mounting substrate 11. In this embodiment, the thickness of the resin film 12 is set to 250 µm.

Next, in the vacuum packing step, the collective mounting substrate 11, the mounted SAW elements 2, and the resin film 12 are put in a bag 13 for vacuum packaging, and the inside of the bag 13 is deaerated under reduced pressure, for example 500 Pa or less to be hermetically sealed by heat sealing. As for the shape of the bag 13, a bag is listed as being suitable, which has a substantially rectangular shape and an opening formed at one end thereof, the thickness of the bag 13 is being of the order of 80  $\mu m$ .

As for the bag 13, it should be a bag that has at least flexibility, a gas-barrier property, and a heat sealing

property, and can contain the collective mounting substrate 11 or the like. For example, a bag having a multi-layered structure is listed as being suitable that is formed of a polyester film with an excellent gas-barrier property and heat resistance withstanding the temperature during heat sealing or curing, for example 180°C to 250°C, as an outer layer, and a polyethylene film with heat sealing property as an inner layer (sealant layer).

Thus, the temperature of the heater 15 for heat sealing to be hereinafter described should exceed the fusing temperature of the inner layer, and therefore, in this embodiment, is set to be the order of 150°C to 200°C. In addition, it may be a bag that can maintain a sealing or hermetically sealing property, instead of the heat sealing property, by means of fixing with clips or the like.

Moreover, in the multi-layered structure, in order to improve the gas-barrier property, an aluminum layer should be provided as an intermediate layer. As another example of the material for an exterior bag, polyimide and polyamide with excellent heat resistance are listed as being suitable. As another example of the material for an interior bag, polypropylene-based materials with a heat sealing property are listed as being suitable.

As shown in FIG. 3, during the hermitical sealing, the bag 13 into which the collective mounting substrate 11, the

SAW elements 2, and the resin film 12 have been placed, is placed on a placing bed 14 within a hermetically sealed container 10. The inside of the bag 13 is deaerated by a vacuum pump so that the inside of the container 10 enters a vacuum state (500 Pa or less), and the surrounding area of the opening of the bag 13 is fused by a fusing heater (heat sealer) 15 from the both sides to close the opening. As for the vacuum state (under reduced pressure), it should be of a pressure smaller than a pressure present in a pressurized state or a reduced pressure in the curing step to be hereinafter described, however, it is preferable to be 500 Pa or less.

When the closed bag 13 is taken out into the atmospheric pressure from the hermetically sealed container 10, as shown in FIG. 1(b), the bag 13 enters a state in which the bag 13 contacts the outsides of the collective mounting substrate 11, the SAW elements 2, and the resin film 12 due to the pressure difference.

In addition, as for a process other than the hermetically sealing process, a process is listed as being suitable that deaerates the inside of the bag 13 by inserting a metal pipe connected to a vacuum pump into the opening of the bag 13 in an air-tight manner. In this case, the parts of the opening facing each other also closely contact each other, and the opening should be closed by

fusing the surrounding area of the opening by a heat fusing heater (heat sealer) 15 while pulling out the metal pipe in this state.

Subsequently, the sealing step is implemented, which includes an infiltrating step and a curing step. As shown in FIG. 1(c), in the infiltrating step, the resin film 12 is softened by being heated together with the bag to a temperature, for example, below the curing temperature of the resin film 12, in this embodiment below 150°C, or 100°C to 140°C.

Thereby, the softened resin film 12 is caused to infiltrate between the individual SAW elements 2 mounted on the collective mounting substrate 11 vacuum packed inside the bag 13 by means of the pressing force due to the pressure difference between the inside and the outside of the bag 13. As a result, the SAW elements 2 are covered with the sealing resin precursor 4a formed from the resin film 12 and sealed.

At this time, the top of the resin film 12 is kept substantially parallel with the collective mounting substrate 11 due to the tensile force of the bag 13, and becomes almost planar when the infiltration is completed.

Next, in the curing step, the SAW elements 2 and the collective mounting substrate 11 are further heated to the curing temperature of the sealing resin precursor 4a formed

from the resin film 12, 150°C in this embodiment, and the sealing resin precursor 4a is cured. As the result, as shown in FIG. 1(d), the sealing resin part 4 covering the SAW elements, is formed.

As shown in FIG. 4, in the curing step, the collective mounting substrate 11, the SAW elements 2, and the sealing resin precursor 4a, vacuum packed inside the bag 13, are placed within an inner space 16a of a hermetically sealed container 16. Here, it is preferable to apply a pressure to the bag 13 in the inner space 16a by means of a pressurized medium 17 whose pressure is controlled by a pressure control part 18 via the phenomenon of equal pressure application. As for the pressurized medium, air, water, oil, and the like are listed as being suitable. The pressure control may be implemented by any process, as long as a suitable pressure can be applied to the bag 13 under vacuum. The pressure regulation may be either pressurization that causes the pressure to be higher than atmospheric pressure, or depressurization that causes the pressure to be lower than atmospheric pressure.

According to the curing step, if the space 5 is adequately formed below the SAW elements 2, or if, using a high-viscosity resin, the sealing resin part 4 is also intended to be infiltrated between the SAW element 2 and the collective mounting substrate 11, the pressure applied on

the sealing resin precursor 4a through the bag 13 should be controlled by regulating the surrounding pressure during curing. Since such a pressure control can be implemented, the tolerance level with respect to the aspect or shape of the sealing resin part 4 becomes wider. The shape or size of the space 5 can also be easily controlled.

In the sealing resin part 4 cured by such a curing step, a concave portion with a depth of the order of several  $\mu m$  occurs at the border line part between the neighboring SAW elements. However, the concave portion does not cause any special problem during the dividing step to be described hereinafter. In order to avoid the occurrence of the concave portion, the thickness of the resin film 12 to be used should be larger.

Thereafter, in the above mentioned dividing step, the SAW elements 2 resin-sealed by the sealing resin part 4 are taken out from the bag 13, and as shown in FIG. 1(e), the collective mounting substrate 11 is divided into individual SAW elements 2 along virtual scission lines 9 by a suitable process, for example, a dicing process, cutting/breaking, or the like.

As mentioned above, in the manufacturing method of the present invention, the SAW elements 2 are sealed by superposing the SAW elements 2, the collective mounting substrate 11, and the resin film 12 on each other, and

subjecting them to vacuum packing by means of the bag 13, and then, the softened resin film 12 is cured. Thereby, since the air within the bag 13 is discharged, a lamination CSP-type SAW device in which voids do not occur, can be obtained.

In the manufacturing method, apparatuses to be used are only a simple vacuum packing machine and a small heating oven. Thus, using one collective mounting substrate 11 while avoiding the occurrence of the voids, several hundreds to several thousands of SAW devices can be manufactured in one batch and at a low cost.

In addition, when a resin film having filler with a small particle size and a resin with low elasticity are used to form the resin film 12, the resin can also be caused to infiltrate the gap between the SAW element 2 and the collective mounting substrate 11.

Moreover, if, as in a SAW device including a SAW filter, a vibration space is required between the collective mounting substrate 11 and the SAW element 2, it is preferable to use a resin film 12 having fillers with a maximum particle size larger than the gap between the collective mounting substrate 11 and the SAW element 2, and high elasticity during softening. Thereby, it is possible to adequately form a space 5 between the collective mounting substrate 11 and the SAW element 2. In addition, by

suitably setting the thickness of the resin film 12 to be used, the production thickness of the obtained SAW device can be controlled.

Hereinafter, the effects of the manufacturing method according to this embodiment will be described.

In the manufacturing method, by using a simple vacuum apparatus and a simple technique, sealing can be implemented at a high productivity rate and at a low cost, and, by using an atmospheric pressure, the entire surface of the bag 13 can be evenly depressed. Accordingly, the manufacturing method is negligibly affected by the thickness variation of the collective mounting substrate 11 or the SAW element 2 as compared with a roller technique or a press technique.

Further, in the manufacturing method, it is not required to form many holes for vacuuming, thus enabling to be of a compact size, and the sealing resin precursor 4a formed from the resin film 12 is pushed slowly between the SAW elements by atmospheric pressure, thus the SAW elements to be products are not subjected to temperature or pressure that is greater than required. Therefore, it is possible to prevent pyroelectric breakdown among SAW elements, conductive defect of parts of the bump electrodes 3, chips among SAW elements, or the like.

Moreover, in the manufacturing method, the all of the SAW elements can be covered with the sealing resin part 4,

thus enabling a sufficient sealing thickness. Accordingly, in the manufacturing method, sealing property can be improved as compared with the case using a thin film, and, at the same time, the surface areas of the packaging substrate 1 and the top of the sealing resin part 4 can be caused to be substantially equal to each other. Thus, it is easy to ensure the mountability of the obtained SAW device.

Next, another embodiment according to the present invention will be described. In the arranging step, the entire surface of one side of the resin film 12, the entire outer surface, may be adhered with a parting sheet 19. As for the material of the parting sheet 19, a material should be used that has heat resistance equal to that of the outer layer of the bag 13 or more, and small affinity, or adhesiveness, to the inner layer of the bag 13 or the sealing resin part 4. For example, PET (polyethylene phthalate) or the like can be listed as being suitable.

In this case, as shown in FIG. 5, after forming the sealing resin part 4 by softening and curing the resin film 12, the parting film 19 is released. Accordingly, adhesion of contaminants such as dirt to the surface of the sealing resin part 4 or occurrence of unevenness during the curing procedure can be prevented, and even if heated to the curing temperature, it is possible to prevent the inner layer of the bag 13 and the sealing resin part 4 from adhering to

each other, thus, enabling the manufacturing steps to be simplified.

Moreover, since the surface roughness of the parting film 19 at the resin film 12 side is transferred to the surface of the sealing resin part 4 formed from the resin film 12, a package top of the sealing resin part 4 with a good surface condition can be obtained, thus, enabling good laser printing to the package top without a preliminary treatment.

In addition, when the relationship between the surface roughness  $(\mu m)$  of the package top of the sealing resin part 4 and the recognition rate in the laser printing (%) was investigated by variously changing the surface roughness, results as shown in FIG. 6 were obtained. In addition, the value of the surface roughness is a value measured using a non-contact three dimensional surface roughness measuring machine. Thereby, it is understood that it is preferable for the surface roughness of the resin film 12 side of the parting sheet 19 to be within a range of 0.01  $\mu m$  to 10  $\mu m$ .

On the other hand, there is a situation in which an electronic component such as the SAW element 2 or a semiconductor element 22 is bonded on the packaging substrate or a package by facedown bonding, and the surroundings are sealed with the sealing resin part. In such a situation, after being cured, when a lot number or a

mark of the product is printed on the sealing resin part 4, the printing can not be implemented clearly due to the unevenness or the presence of contaminants on the surface of the sealing resin part 4. In the related art, as a countermeasure, a process in which after further coating a printing resin with a color developing property on the sealing resin part, the laser printing was implemented, has been used. As a result, there has been a problem that the additional steps resulted in an increase in cost.

In order to address such problems, the SAW elements 2 bonded on the collective mounting substrate 11 by face down bonding should be covered with the resin film 12, and, further the parting sheet 19 should be placed on the resin film 12 to soften and cure the resin film 12. Thereby, the unevenness and contamination of the surface (top) of the sealing resin part 4 formed from the resin film 12 can be prevented from occurring during curing.

Thereby, it is possible to directly implement laser printing on the sealing resin part 4 without subjecting the sealing resin part 4 to a special processing, thus, enabling cost reduction while ensuring impressability.

In addition, although in the embodiment, as an electronic component, an example of the SAW element was listed, the electronic component is not limited to the above embodiment, rather, for example, as shown in FIG. 7, the

semiconductor element 22 may be used instead of the SAW element 2. If the semiconductor element 22 is used, since it is not required to ensure the existence of the space 5 shown in FIG. 2, the space 5 may be filled with the sealing resin part 4 as an underfilling material.

Moreover, in the infiltrating step, an example using pressurization by atmospheric pressure to the reduced pressure within the bag, was listed, however, as shown in FIG. 8, heating and pressing rollers 26, 26 may be used. Thus, the infiltrating step is intended to be implemented by placing the resin film 12 on the SAW elements 2 mounted on the collective mounting substrate 11 through the bump electrodes 3, placing the contents contained within the bag 13 on a flat plate 24, and transferring the bag 13 together with the flat plate 24 between the two heating and pressing rollers 26, 26.

Moreover, as shown in FIG. 9, pressurization by inserting the bag 13 in a press frame 28c of a press machine 28 may also be used. The infiltrating step using the above pressurization is a process in which the bag 13 containing the collective mounting substrate 11, the SAW elements 2, and the resin film 12, are placed on the lower bed 28b of the press machine 28, and the resin film 12 is buried by pressing the bag using a tool such as the press frame 28c attached to the rear surface of the upper press 28a, while

the resin film 12 is heated from above by processing the upper press 28a, to form the sealing resin part 4 from the resin film 12.

Further, during the vacuum packing step, in order to deaerate air effectively from the gap between the resin film 12 and the collective mounting substrate 11, a spacer should be placed so as to form a gap between the surroundings of the collective mounting substrate 11 and the bag 13 that is an adhesive film, to provide an air hole (air path).

Moreover, a part of the collective mounting substrate 11 or a part of the thermally softened adhesive resin film 12 may be provided with the air hole. In order to ensure the adhesiveness by means of atmospheric pressure after vacuum packing step, the air hole should be opened anywhere of the space formed between the resin film 12 and the collective mounting substrate 11.

Moreover, in the vacuum packing step, after replacing the contents of the bag 13 with inert gas such as dry nitrogen, deaeration may be implemented further. Moreover, as for the process for hermetically sealing the bag 13, thermal fusioning is preferable, however, any process that can block entry of the surrounding air, such as adhesion or contact bonding using a tool may be used.

Moreover, if a space 5 is formed under the SAW element 2, in order to minimize the infiltration amount of the

sealing resin part 4, sealing should be implemented with suitable residual air left by regulating the degree of vacuum during vacuuming. As for the degree of vacuum at this time, it differs depending on the volume of the space 5 to be formed or the shape of the product, however, it is preferable to be 100 Pa to 500 Pa.

In this manner, by causing the residual air to be left, namely, by controlling the air amount during dearation of the inside of the bag 13, an effect similar to those of the disclosed embodiments can be attained, and a repulsive force occurs within the space 5 during sealing, thus causing the space 5 to be formed easily.